

U.S. Department of Commerce, Patent and Trademark		Atty. Docket No.			Patent No.		
INFORMATION DISCLOSURE STATEMENT BY REQUESTOR		SENS.005US0			10/056,906		
		Applicant(s)					
(Use several sheets if necessary)		Wayne G. Renken					
		Filing Date			Group		
		January 24, 2002			2856		
<b>U.S. Patent Documents</b>							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
<i>CDK</i>	001	6,542,835	04/01/2003	Mundt			
<b>U.S. Published Patent Application Documents</b>							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
<i>CDK</i>	002	2002/0193957	12/19/2002	Freed		<i>RECEIVED OCT 21 2003 MAIL ROOM</i>	
<i>CDK</i>	003	2002/0172097	11/21/2002	Freed		<i>RECEIVED OCT 21 2003 MAIL ROOM</i>	
<i>CDK</i>	004	2002/0177916	11/28/2002	Poolla		<i>RECEIVED OCT 21 2003 MAIL ROOM</i>	
<i>CDK</i>	005	2002/0177917	11/28/2002	Polla		<i>RECEIVED OCT 21 2003 MAIL ROOM</i>	
<i>CDK</i>	006	2002/0161557	10/31/2002	Freed		<i>RECEIVED OCT 21 2003 MAIL ROOM</i>	
<b>Foreign Patent Documents</b>							
						Translation	
	Document	Date	Country	Class	Subclass	Yes	No
<i>CDK</i>	007	WO02/17030A2	02/28/2002	PCT			
<i>CDK</i>	008	WO02/17030A3	02/28/2002	PCT			
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
<i>CDK</i>	009	Prov. Pat. App. No. 60/285,613 filed 04/19/2001; Freed et al.; "Firmware, Methods, Apparatus, and Computer Program Products for Wafer Sensors"					
<i>CDK</i>	010	Prov. Pat. App. No. 60/285,439 filed 04/19/2001; Freed et al.; "Methods Apparatus, and Computer Program Products for Obtaining Data for Process Operation, Optimization, Monitoring, and Control"					
<i>CDK</i>	011	Freed et al.; "Autonomous On-Wafer Sensors for Process Modeling, Diagnosis, and Control", IEEE Transactions on Semiconductor Manufacturing, Vol. 14, No. 3, Aug. 2001, pp. 255-264.					
<i>CDK</i>	012	Freed; "Wafer-Mounted Sensor Arrays for Plasma Etch Processes", Dissertation, Univ. of CA, Berkeley, Fall 2001					
Examiner <i>CDK</i>	Date Considered <i>1/6/2004</i>						
*EXAMINER: Initial in reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.							

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<b>U.S. Patent Documents</b>								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
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<i>CDK</i>	006	2002/0109590	8/2002	Parsons				
<b>Foreign Patent Documents</b>								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
<i>CDK</i>	007	WO00/68986	2000	PCT				
<i>CDK</i>	008	EP 1 014 437 A2	6/2000	EP				
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>								
<i>CDK</i>	009	International Search Report, PCT/US03/00751, 08/01/2003.						
<i>CDK</i>	010	Baker et al., "A Novel <i>In Situ</i> Monitoring Technique for Reactive Ion Etching Using a Surface Micromachined Sensor," IEEE Transactions on Semiconductor Manufacturing, Vol. 11, No. 2, May 1998, pp. 254-64.						
Examiner <i>CDK</i>		Date Considered <i>1/6/2004</i>						